

DO NOT ENTER: /M.A./

06/04/2008

DOCKET NO: 263788US2PCT

IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF :
KEISUKE KAWAMURA, ET AL. : EXAMINER: ARANCIBIA, M. G.
SERIAL NO: 10/519,475 :
FILED: DECEMBER 28, 2004 : GROUP ART UNIT: 1792
FOR: APPARATUS FOR PLASMA :
PROCESSING, METHOD OF
PROCESSING SUBSTRATE
THEREWITH, APPARATUS FOR
PLASMA-ENHANCED CHEMICAL
VAPOR DEPOSITION, AND METHOD
FOR FILM FORMATION THEREWITH

AMENDMENT UNDER 37 C.F.R. § 1.116

COMMISSIONER FOR PATENTS
ALEXANDRIA, VIRGINIA 22313

SIR:

In response to the Office Action dated January 29, 2008, please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 8 of this paper.